PATENT COOPERATION TREATY

From the INTERNATIONAL SEARCHING AUTHOL	RTTY			ild.
То:			PCT	anslation
			RITTEN OPINION OF TH TIONAL SEARCHING AU	ŀΕ
			(PCT Rule 43bis.1)	
		Date of mailing (day/month/year)		
Applicant's or agent's file reference		FOR FURTHER ACTION		
pf-3291			See paragraph 2 below	
International application No.	International filing date ((day/month/year) Priority date (day/month/year)		r)
PCT/JP2004/007791	28.05.2004		29.05.2003	
Applicant NEC CORPORATION				
Box No. IV Lack of the Box No. V Reasoned applicated Box No. VI Certain do	dishment of opinion with remity of invention statement under Rule 43bis ity: citations and explanation occuments cited effects in the international appropriations on the international appropriation of the international appropriation is in a grant Authority ("IPEA") excepte chosen IPEA has notified	I(a)(i) with regard to an supporting such at plication and application ande, this opinion we pt that this does not a d the International Bu	vill be considered to be a wr. pply where the applicant choose	strial itten opinion of the es an Authority other
If this opinion is, as provided above written reply together, where app PCT/ISA/220 or before the expiration for further options, see Form PCT/	ropriate, with amendments on of 22 months from the pr	before the expiration	on of 3 months from the date	
3. For further details, see notes to For	m PCT/ISA/220.			
Name and mailing address of the ISA/JP		Authorized officer		
Facsimile No.		Telephone No.		

→→→ Sughrue, Mion

WRITTEN OPINION OF THE INTERNATIONAL SEARCHING AUTHORITY

International application No. PCT/JP2004/007791

Bax	x No. 1 Basis of this opinion	
1.	With regard to the language, this opinion has been established on the basis of the international application in the langua filed, unless otherwise indicated under this item.	ge in which it was
	This opinion has been established on the basis of a translation from the original language into the following language	ge
	. which is the language of a translation furnished for the purposes of internation	
	Rule 12.3 and 23.1(b)).	
2.	With regard to any nucleotide and/or amino ocid sequence disclosed in the international application and necessal invention, this opinion has been established on the basis of:	ry to the claimed
	a. type of material	
	a sequence listing	
	table(s) related to the sequence listing	·
	b. format of material	
	in written format	
	in computer readable form	
	c. 'time of filing/furnishing	
1	contained in the international application as filed.	
	filed together with the international application in computer readable form.	•
	furnished subsequently to this Authority for the purposes of search.	
3.	In addition, in the case that more than one version or copy of a sequence listing and/or table(s) relating theret furnished, the required statements that the information in the subsequent or additional copies is identical to that i filed or does not go beyond the application as filed, as appropriate, were furnished.	o has been filed or n the application as
4.	Additional comments:	
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	·	
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WRITTEN OPINION OF THE INTERNATIONAL SEARCHING AUTHORITY

International application No.
PCT/JP2004/007791

Box No.	IV Lack of unity of invention	
ı. 🛛	In response to the invitation (Form PCT/ISA/206) to pay additional fees the applicant ha)E:
	paid additional fees	
	paid additional fees under protest	
	not paid additional fees	
2.	This Authority found that the requirement of unity of invention is not complied with additional fees.	and chose not to invite the applicant to pay
3. Th	us Authority considers that the requirement of unity of invention in accordance with Rules I	13.1, 13.2 and 13.3 is
	complied with	
	not complied with far the following reasons:	
	Claims 1 to 23 have a common feature of relating to formed on an insulating film located on a substrate, but bee known from reference sources, this feature cannot be consificature. Therefore, there is no special technical feature for ligroup described by claims 1 to 23 so as to form a single gethis reason, the inventions of the groups described in claim satisfy the requirement of unity of inventions. Furthermore, the number of groups of inventions segmental inventive concept that are described in the claims of application, that is, the number of inventions are examined. From the special features of the inventions described are inferred that four inventions divided into [1-18], [19] described in the claims of the international patent application. The invention of claims [1-18] is considered in greefeature described in claim 1 is described in [JP 2000-1831-Electric Co., Ltd.)], it cannot serve as a special technical feature describe four inventions divided into [1, 2], [3-9, 13-15, 17]. Furthermore, the examination of the inventions describe four inventions divided into [1, 2], [3-9, 13-15, 17]. Furthermore, the examination of the inventions described in the cannot serve as a special technical feature because that those inventions are linked in the insulating barrier layer comprising silicon and an organic for the furthermore, the examination of the inventions described in the structure of multilayer wiring and a method for manufacture of multilayer wiring and a metho	cause this feature is well idered as a special technical linking the inventions of a general inventive concept. For as 1 to 23 obviously do not so linked as to form a single of the international patent dibelow. The independent claims, it 9, 20], [21, 23], [22] are ion. The inventions detail below. Because the 66 A, Full text (Nippon feature linking the inventions e, claims [1-18] apparently 7, 18], [10-12], and [16]. Scribed in claims [1, 2], [10-terms of relating to an compound. Scribed in claims [1, 2], [21, terms of relating a wiring are thereof. The inventions of [1, 2, 10-12].
1. 0	Consequently, this opinion has been established in respect of the following parts of the intern	national application:
	all parts	
[the parts relating to claims Nos.	

Box No. V

Reasoned statement under Rule 43bis.1(a)(i) with regard to novelty, inventive step or industrial applicability;

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International application No.
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	citations and explanations supporting such statement			
ı.	Statement			
	Novelty (N)	Clains	5-20, 22, 23	YES
			1-4, 21	NO
	Inventive step (IS)	Claims		YES
		Claims	1-23	NO
	Industrial applicability (IA)	Claims	1-23	YES
	·	Claims		NO
2.	Citations and explanations: Document 1: JP 2000-1: Document 2: WO 2002/ drawings	058134	(NEC Corp.), 30 June 2000, Full text, all drawings Al (STMICROELECTRONICS SA), 25 July 2002, Full (

Document 3: WO 2001/054190 A1 (ADVANCED MICRO DEVICES), 26 July 2001. Full text, all drawings

Document 4: TADA M. et al. Barrier-metal-free (BMF), Cu dual-damascene interconnects with Cuepi-contacts buried in anti-diffusive, low-k organic film, 2001 Symposium on VLSI Technology, 12 June 2001, pp. 13-14

Document 5: JP 2002-83870'A (Tokyo Electron, Ltd.), 22 March 2002, Full text, all drawings

Claims 1 to 3

The inventions of claims 1 to 3 do not appear to possess novelty or involve an inventive step based on document 1, document 2, and document 3.

Claim 4

The invention of claim 4 does not appear to possess novelty or involve an inventive step based on document 2. In the invention described in document 2, the films corresponding to the first insulating film and second insulating film of the invention of the present application are inorganic films. Therefore, the content of carbon in the insulating barrier film comprising an organic substance is apparently higher than that of the first and second insulating films.

Furthermore, the invention described in claim 4 does appear to involve an inventive step based on document 3. In the invention described in document 3, forming the film corresponding to the first insulating film from an inorganic film would be easy for a person skilled in the art.

Claims 5, 6, 17, 18

The inventions of claims 5 and 6 do not appear to involve an inventive step based on document 2 and document 3. Forming the film corresponding to the second insulating film in the invention described in document 2 and forming the film assumable as the first insulating film and second insulating film in the invention described in claim 3 as inorganic films could be easily conceived of by a person skilled in the art.

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Box	No. VI	Certain documents cited			
I.	Certain publ	lished documents (Rule 43bis.) an	d 70.10)		
		Application No. Patent No.	Publication date (day/month/year)	Filing date (day/month/year)	Priority date (valid claim) (day/month/war)
	200	4-200203 N	15.07.2004	16.12.2002	
	[EX	:]			
	200	4-193326 A/	08.07.2004	11.12.2002	
	[EX	3			•
	200	3-347403 A	05.12.2003	30.05.2002	
	[EX	:]			

Non-written disclosures (Rule 43bis.), and 70.9)

Kind of non-written disclosure

Date of non-written disclosure (day/month/year)

Date of written disclosure referring to non-written disclosure (day/month/year)

WRITTEN OPINION OF THE

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International application No.

→→→ Sughrue, Mion

	INTERNATIONAL SEARCHING AUTHORITY	PCT/JP2004/007791		
Box No. VIII	Certain observations on the international application			
The following the description.	observations on the clarity of the claims, description, and drawings or on are made:	the question whether the claims are fully supported by		
	Mutual arrangement of "the third insulating film	", "fourth insulating film", and "via		
interlayer insulating film" in claims 5 and 9 is not clear.				
	•			
	•			
		·		

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International application No.
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Supplemental Box

In case the space in any of the preceding boxes is not sufficient. Continuation of V.2:

As for claims 17, 18, making the films corresponding to the first and second insulating films from the same material and specifically limiting this material to SiCN or the like could be easily conceived of by a person skilled in the art.

Claims 7, 8, 10, 11, 16

The inventions of claims 7, 8, 10, 11, 16 do not appear to involve an inventive step based on document 2 and document 3. Insulating films comprising Si-O bonds are well known as insulating films comprising an organic compound. Furthermore, the content of silicon atoms can be appropriately set by a person skilled in the art.

Claim 9

The invention of claim 9 does not appear to involve an inventive step based on document 2 and document 3. Making the films corresponding to the third insulating film and fourth insulating film from the same material in the inventions described in document 2 and document 3 could be easily conceived of by a person skilled in the art.

Claims 12-15

The invention described in document 12 does not appear to involve an inventive step based on document 2, document 3, and document 4. Document 4 discloses that divinylcyclohexane benzocyclobutene has a barrier property against the diffusion of Cu. Therefore, employing the technology described in document 4 as a barrier insulating film with the object of preventing the diffusion of copper in the inventions described in document 2 and document 3 could be easily conceived of by a person skilled in the art. Furthermore, with respect to the inventions described in claims 13-15, the material for an interlayer insulating film or an etching stopper film can be appropriately selected from well-known materials and limiting the range of materials as described in claims 3-15 could have easily been conceived of by a person skilled in the art.

Claims 19, 20

The inventions of claims 19 and 20 do not appear to involve an inventive step based on document 5. Using a porous interlayer insulating film with the object of reducing the dielectric constant of the interlayer insulating film in the invention described in document 5 could have easily been conceived of by a person skilled in the art.

Claim 21

The invention described in claim 21 does not appear to possess novelty or involve an inventive step based on document 2.

Claim 22

The invention described in claim 22 does not appear to involve an inventive step based on document 2. Forming a film corresponding to the second insulating film in the invention described in document 2 could be easily conceived of by a person skilled in the art.

Claim 23

The invention described in claim 23 does not appear to involve an inventive step based on document 2 and document 4. Using a plasma polymerization method disclosed in document 4 as a method for forming a barrier insulating film could be easily conceived of by a person skilled in the art.